

U.S. Department of Commerce, Patent and Trademark Office

(PTO Form 1449 modified)

Docket No.

AMAT/3417/ETCH/SI
LICON/JB1

Serial No.

09/352,008

LIST OF PATENTS AND PUBLICATIONS CITED BY APPLICANT

Applicant
Xu et al.Confirmation No.
Unknown

(Use several sheets if necessary)

Filing Date

Group

July 12, 1999

1763

U.S. Patent Documents

*Examiner Initial		Document Number	Issue Date	Applicant(s) Name	Class	Subclass	Filing Date If Appropriate
ACP	A1	5,332,468	July 26, 1994	Engelhardt	156 216	643 71	September 30, 1992
	A2						
	A3						
	A4						
	A5						
	A6						
	A7						
	A8						
	A9						
	A10						
	A11						
	A12						
	A13						

Foreign Patent Documents

*Examiner Initial		Document Number	Date	Country	Class	Subclass	Translation
	B1						<input checked="" type="checkbox"/>
	B2						<input checked="" type="checkbox"/>
	B3						<input checked="" type="checkbox"/>
	B4						<input checked="" type="checkbox"/>
	B5						<input checked="" type="checkbox"/>

OTHER ART

*Examiner Initial		Including Author, Title, Date, Pertinent Pages, Etc.
ACP	C1	PCT International Search Report dated February 28, 2001
	C2	
	C3	

Examiner

A Powell

Date Considered

4-23-01

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.

U.S. Department of Commerce, Patent and Trademark Office (PTO Form 1449 modified)		Docket No. AMAT/3417/ETCH/SILICON/ JB1	Serial No. 09/352,008
LIST OF PATENTS AND PUBLICATIONS CITED BY APPLICANT		Applicant XU, ET AL.	
(Use several sheets if necessary)		Filing Date JULY 12, 1999	Group 1763
Examiner			

U.S. Patent Documents

*Examiner Initial		Document Number	Issue Date	Applicant(s) Name	Class	Subclass	Filing Date If Appropriate
	A1						
	A2						
	A3						
	A4						
	A5						
	A6						
	A7						
	A8						
	A9						
	A10						
	A11						
	A12						

Foreign Patent Documents

*Examiner Initial		Document Number	Date	Country	Class	Subclass	Translation	
							YES	NO
ACP	B1	JP05308063	11/19/1993	Japan Abstract	H01L	217392	X	
	B2							
	B3							
	B4							

OTHER ART

*Examiner Initial		Including Author, Title, Date, Pertinent Pages, Etc.
ACP	C1	"Role of the chamber wall in low-pressure high-density etching plasmas", O'Neill, J., et al., Semiconductor Research and Development Center, IBM Microelectronics Division, New York, 1994, pgs 497-504.
ACP	C2	"Behavior of F Atoms and CF ₂ Radicals in Fluorocarbon Plasmas for SiO ₂ /Si Etching", Tachibana, K. et al., Depart. of Electronic Science and Engineering, Kyoto University, Japan, 1999, pages 4367-4372.
ACP	C3	"Influence of reactor wall conditions on etch processes in inductively coupled fluorocarbon plasmas", Schaepkens, M., et al., Depart. of Physics, University at Albany, New York, 1998, pages 2099-2107.
Examiner		Date Considered
ACP/Bowell		4-05-01

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U.S. Department of Commerce, Patent and Trademark Office				Docket No. AMAT/3417		Serial No. Unknown	
LIST OF RELEVANT ART CITED BY APPLICANT				Applicant			
(Use several sheets if necessary)				Songlin Xu et al.			
				Filing Date		Class	
				Herewith		Unknown	

U.S. Patent Documents							
*Examiner Initial		Document Number	Issue Date	Name	Class	Subclass	Filing Date If Appropriate
<i>AD</i>	AA	5,242,536	09/07/1993	SCHOENBORN	438	714	_____
<i>AD</i>	AB	5,256,245	10/26/1993	KELLER ET AL.	438	714	_____
<i>AD</i>	AC	5,880,033	03/09/1999	TSAI	438	710	_____
<i>AD</i>	AD	5,453,156	09/26/95	CHER ET AL.	438	695	_____
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						

Foreign Patent Documents								Translation	
		Document Number	Date	Country	Class	Subclass	Yes	No	
	AL								
	AM								
	AN								
	AO								
	AP								

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)		
	AQ	
	AR	
	AS	

Examiner <i>Adwell</i>	Date Considered <i>4-5-01</i>
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